

# Low-Cost Direct Bonded Aluminum (DBA) Substrates

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**Oak Ridge National Laboratory**

**2013 Vehicle Technologies Annual Merit Review  
and Peer Evaluation Meeting**  
**Arlington, VA**  
**14 May, 2013**

**Project ID #:  
PM036**

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# Overview

## Timeline

- **Project start: October 2010**  
(actual funding starts: Jan 2011)
- **Project end: September 2013**
- **Percent complete: 75%**

## Budget

- **Total project funding**
  - DOE 100%
- **FY11: \$200k**
- **FY12: \$200k**
- **FY13: \$130k (\$80k allocated to-date)**

## Barriers\*

- **High cost per kW**
- **Low energy per kg**
- **Low energy density**
- **Insufficient performance and lifetime**

## Targets

- **DOE VTP\* 2020 target: \$3.3/kW**
- **DOE VTP\* 2020 target: 14.1 kW/kg**
- **DOE VTP\* 2020 target: 13.4 kW/l**
- **15 year life**

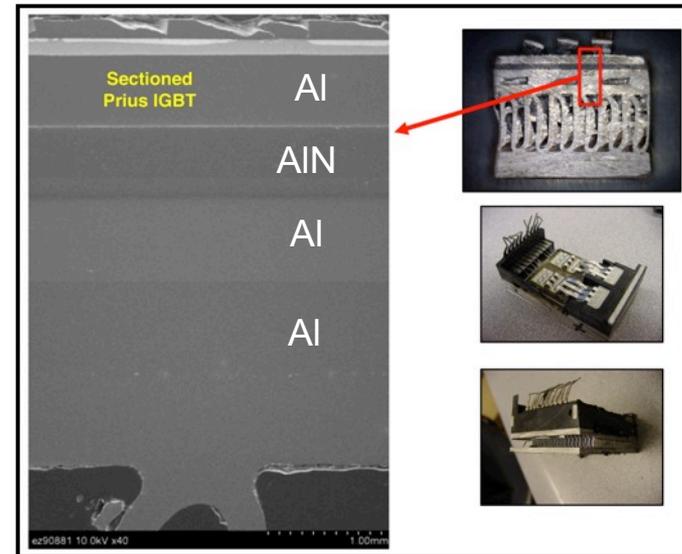
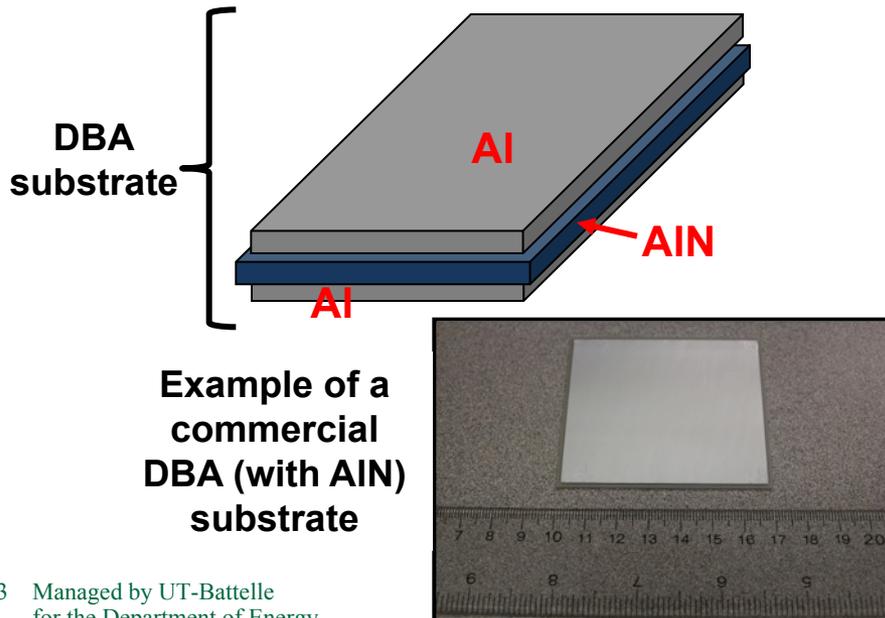
## Partners

- **NTRC – ORNL**
- **Marlow (thermoelectric manuf.)**
- **Materion (metal cladding supplier)**

\* VTP Multi-Year Program Plan 2011-2015

# Objectives

- Develop low-cost, high quality, and thermomechanically robust direct-bonded aluminum (DBA) substrates.
- Use ORNL's in-house unique processing capabilities to fabricate innovative DBA substrates using a process that is amenable for mass production and that produces high adhesive strength of the ceramic-metal interfaces.
- Consider the fabrication and use of low-cost AlN as a potential (and alternative) contributor.



Example of Al to AlN bonding in 2010 Prius IGBT

Photo used with permission of Z. Liang (NTRC/ORNL)

# Milestones

- **FY13 - 1: Complete optimization of fabrication processing parameters for DBA substrates with alumina ( $\text{Al}_2\text{O}_3$ ) and aluminum nitride (AlN) ceramic.**
- **FY13 -2: Complete fabrication of silicon nitride ( $\text{Si}_3\text{N}_4$ ) ceramic substrates with both high mechanical properties and thermal conductivity.**
- **FY13 – 3: Complete development of DBA and/or direct bonded copper (DBC) substrates with high performance silicon nitride ceramics (may not be completed due to budget changes).**

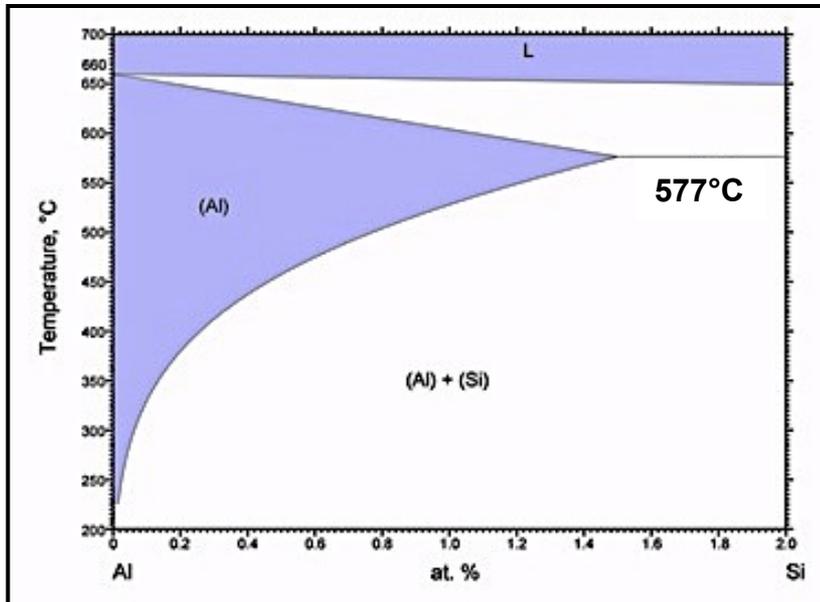
# Technical Approach

- **Study patent and open literature for DBA fabrication.**
- **Identify alternative processing method to fabricate large-sized DBA substrates that has potential for low-cost manufacture. This is the first primary step in creating availability of low-cost DBA substrates.**
- **Benchmark existing commercial DBA substrates for eventual comparison against DBA substrates fabricated in this project. Also, benchmark select commercially available DBC substrates.**
- **Develop  $\text{Si}_3\text{N}_4$  material with both high mechanical and thermal properties for ceramic substrate fabrication.**
- **Develop test method to measure interfacial shear strengths of the Al-ceramic interface.**

# Accomplishments

## Many Bonding Methods Were Considered

Al-Si phase diagram



Al-Si exhibits an eutectic phase at ~577°C

- Transient Liquid Phase (TLP) process via CVD Si film
- Brazing process via Al-Si alloy film

➤ Approaches taken in this subtask:

- Commercial Al-11Si brazing paste (DayBraze 729, Johnson Manufacturing Co.)
- Al-Si alloy foil (All Foils, Inc.)
- Al-Si tape prepared from powders via atomization process (READE Advanced Materials)
- Si tape prepared from powders (Vesta Si)

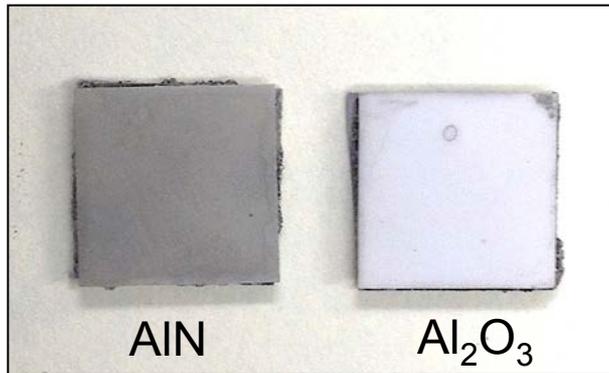
➤ Hot press conditions:

- 580 – 600°C
- 5 MPa
- Argon or N<sub>2</sub>

# Accomplishments (continued)

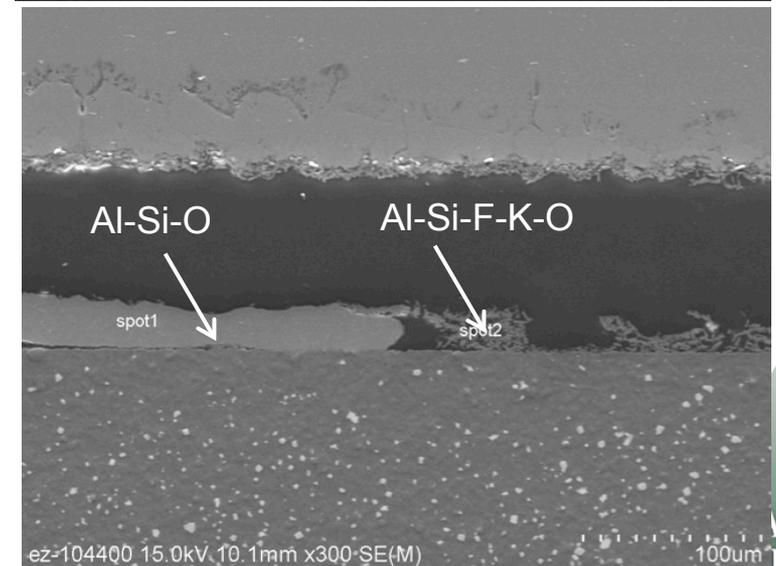
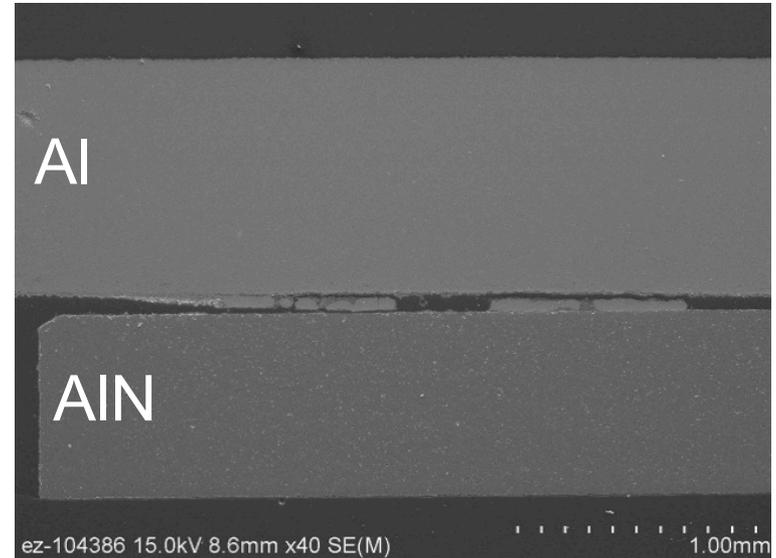
## Insufficient Bonding Resulted in Early Trials

ORNL DBA substrates via  
Al-11Si brazing paste



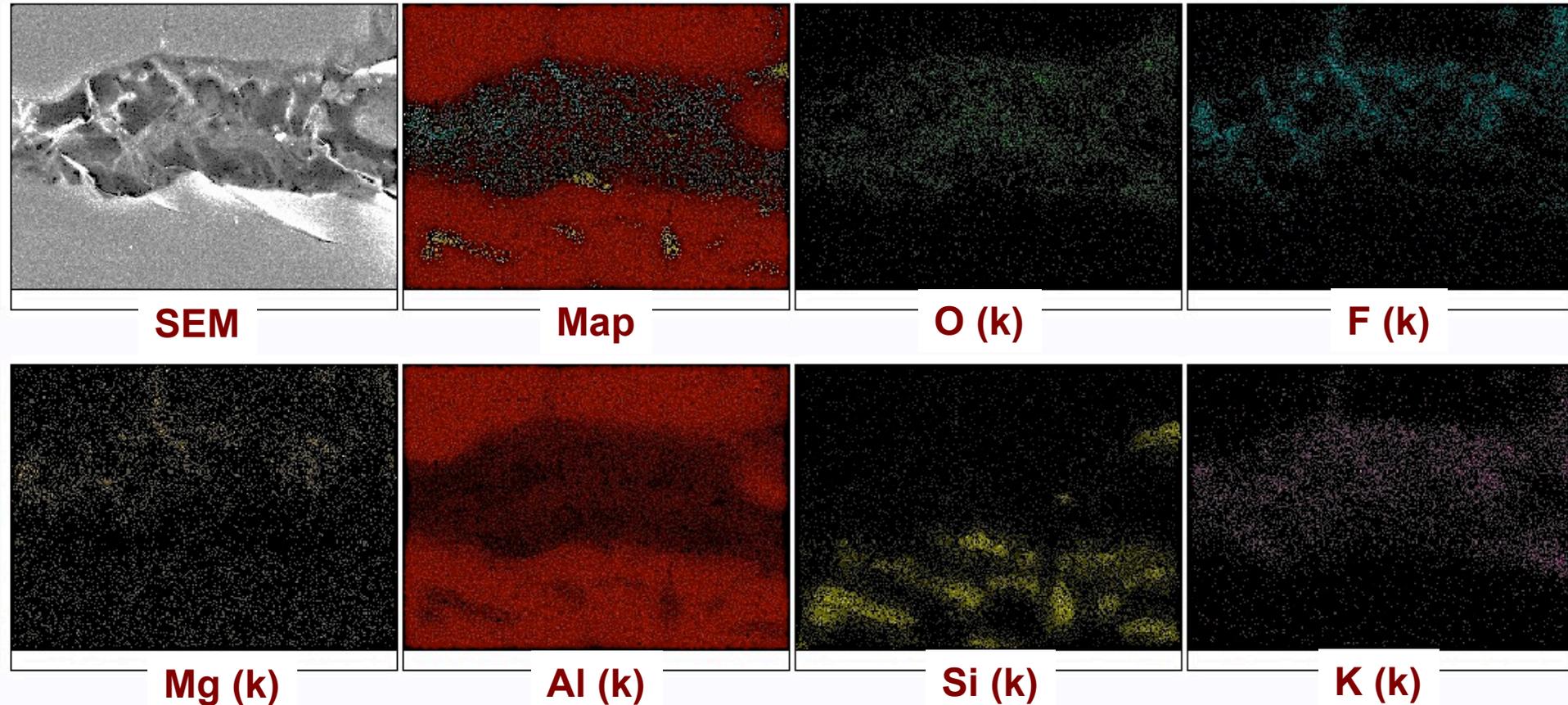
Visual inspection looked sound, but they could be readily peeled off by hand, indicative of poor bonding.

- Low vacuum in the hot-press could cause oxidation of Al plate and paste prior to joining.
- Completed instrumentation of a mechanical testing system with high vacuum furnace.



# Accomplishments (continued)

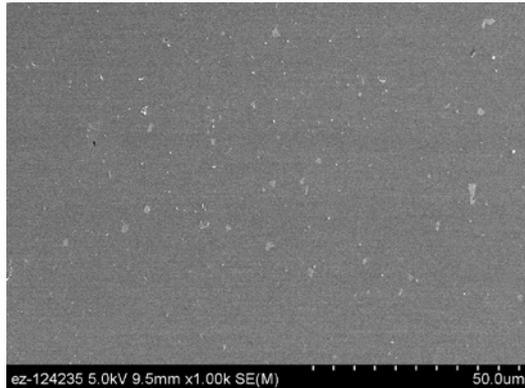
Uncompleted Reaction of Al-Si Paste Combined with High Oxygen Content Were Probably the Cause of Poor Bonding



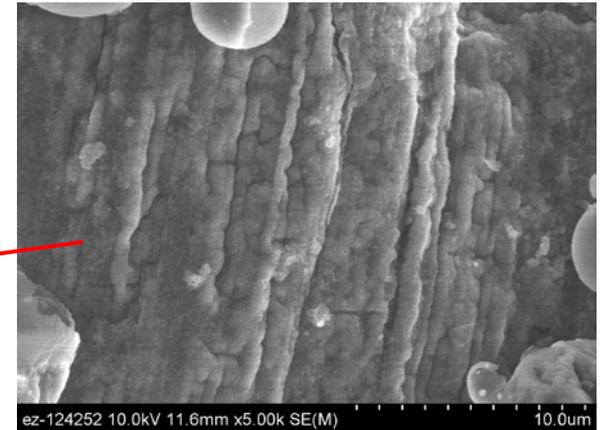
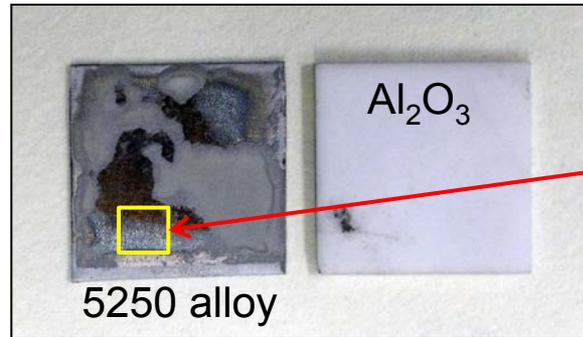
SEM EDAX element map of ORNL DBA substrate bonded with commercial Al-11Si brazing paste

# Accomplishments (continued)

## Poor Wettability Existed Between Both Grades of Al-Si Foil and Ceramic Substrate



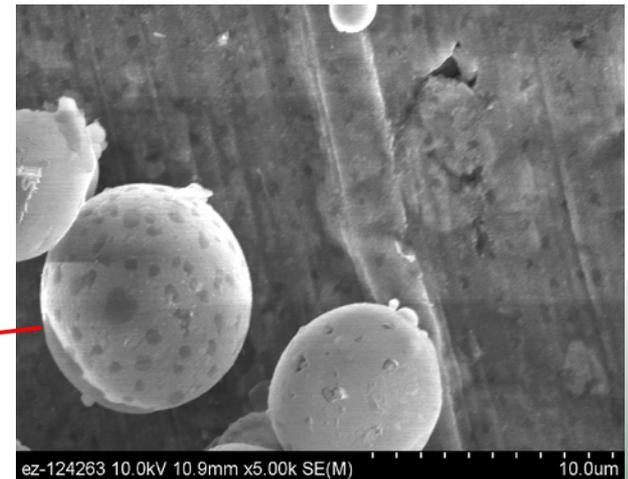
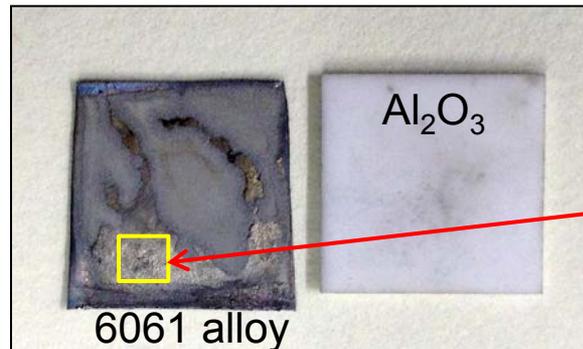
5250 alloy (Al-Mg-Mn-Si)



Hot press at 610°C in N<sub>2</sub>



6061 alloy (Al-Si-Cu-Cr)



SEM micrographs of polished cross section of as-received Al-Si alloy foils

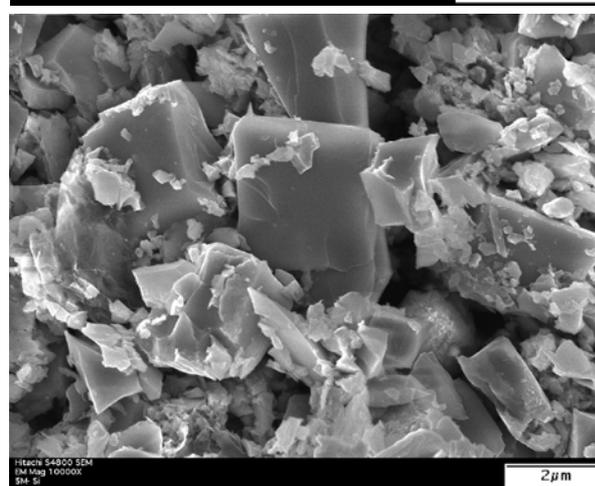
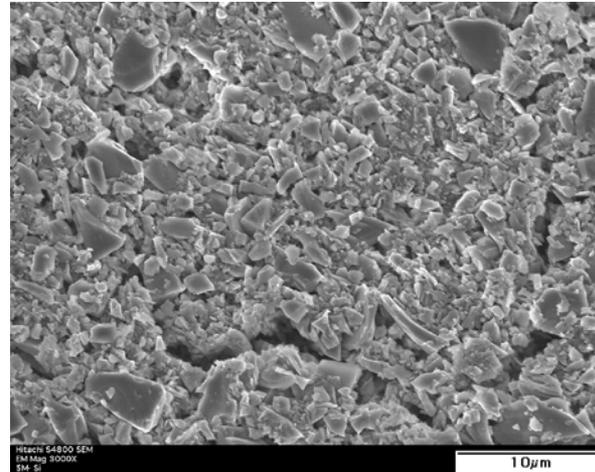
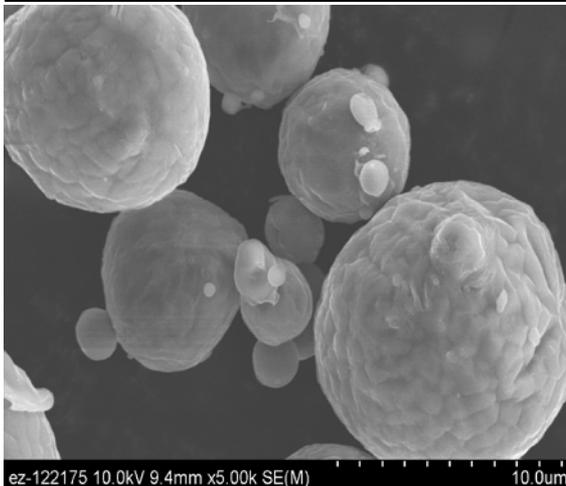
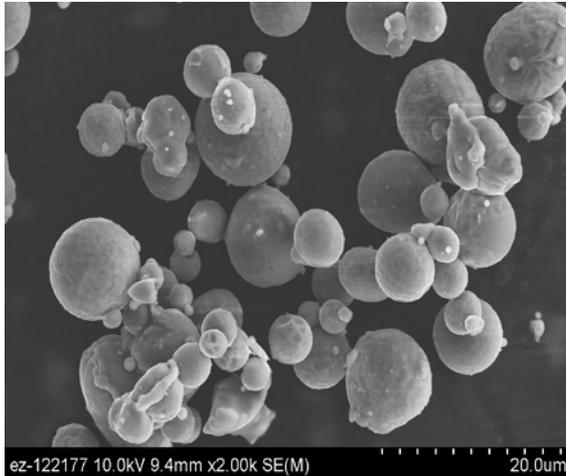
SEM micrographs of Al plate surface after bonding

# Accomplishments (continued)

## Microstructure of Al-Si-Mg and Si Powders

READE Advanced Materials

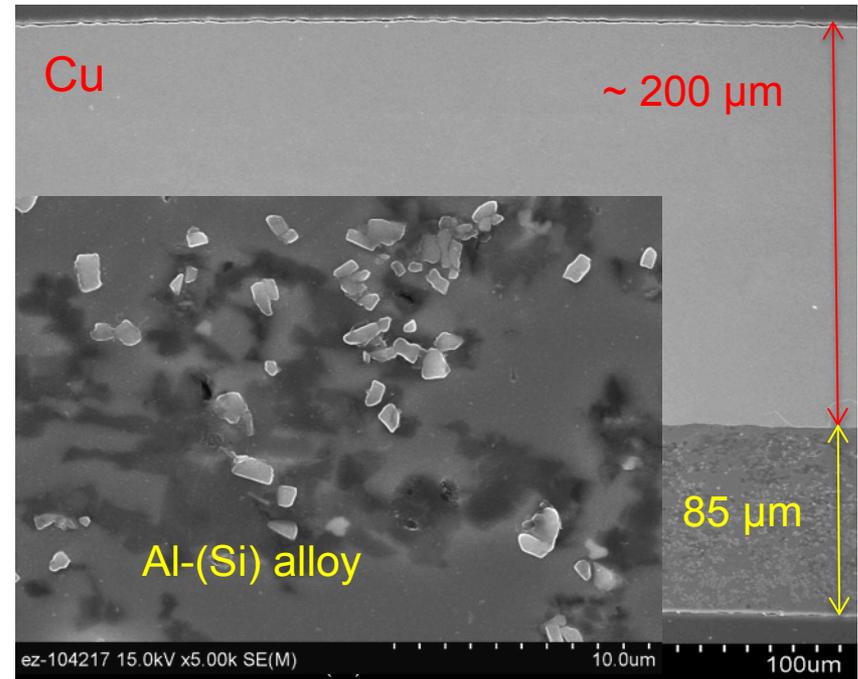
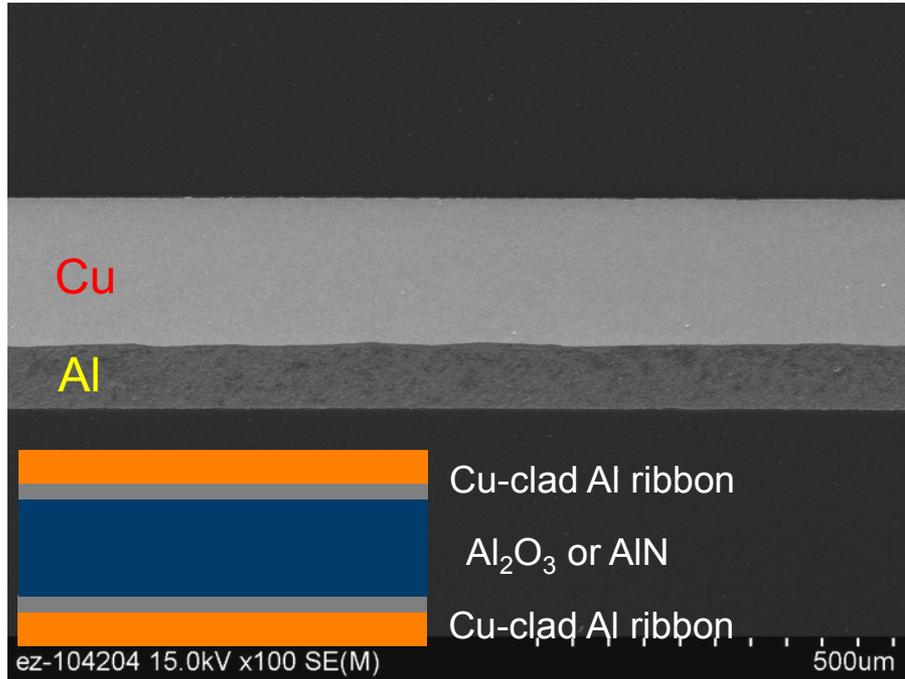
SicoMill® Si powder (Vesta Si)



**Al-Si and Si film prepared by tape casting will be used to bond Al and Al<sub>2</sub>O<sub>3</sub> (AlN) ceramic in the remaining FY13.**

# Accomplishments (continued)

## Cu-clad Al foil was Evaluated as a Candidate Cladding

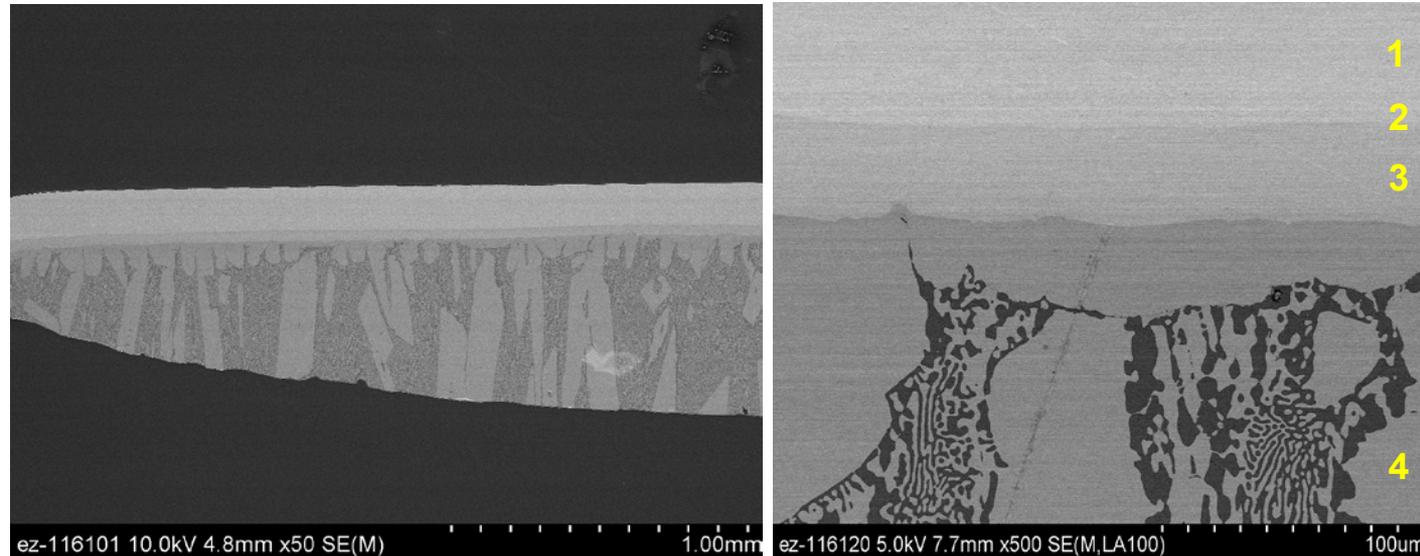


**Developmental Cu-clad Al foil was acquired from Materion Corp., Cleveland, OH.**

- The Cu-clad Al material could eliminate the need for interfacial brazing layer.
- Cu-clad Al material exhibits 45% higher thermal conductivity and 30% higher current density.

# Accomplishments (continued)

## Poor Bonding Resulted Between Cu-Clad Al Foil & Ceramic

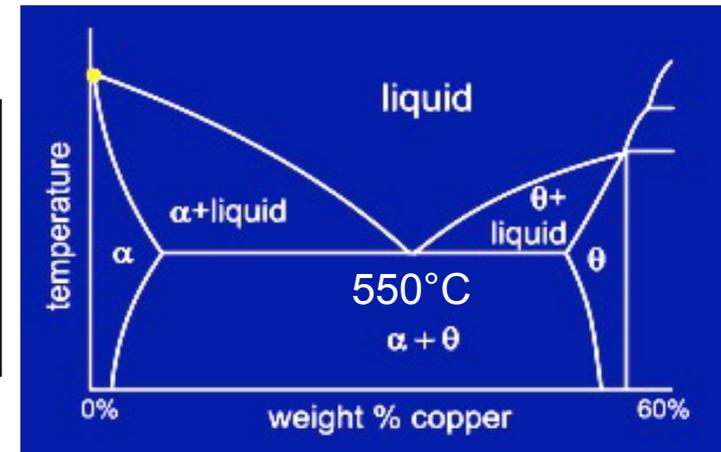


1: 100% Cu  
2: 79%Cu-21%Al  
3: 75%Cu-25%Al

4: 53%Cu-47%Al

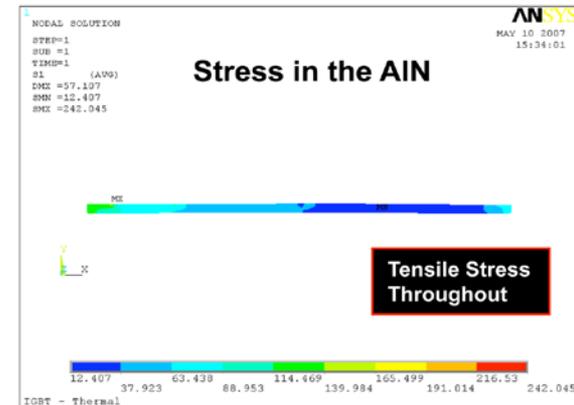
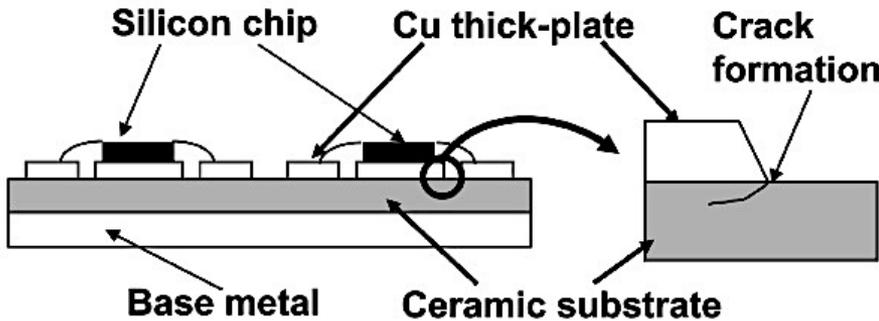
Polished cross section of Cu-clad Al foil after joining

- Cu-Al exhibits an eutectic point at 550°C lower than Al-Si eutectic point of 577°C
- Active brazing alloy might be needed to prevent early Al-Cu eutectic formation

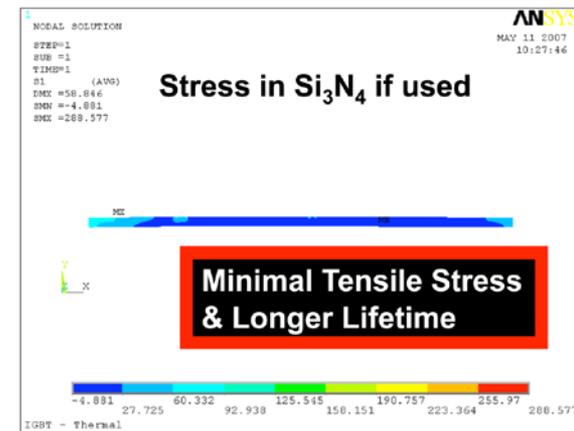


# Accomplishments (continued)

Wide Band Gap Technology (GaN or SiC) Requires High Performance Substrates Such as  $\text{Si}_3\text{N}_4$  DBC Substrates



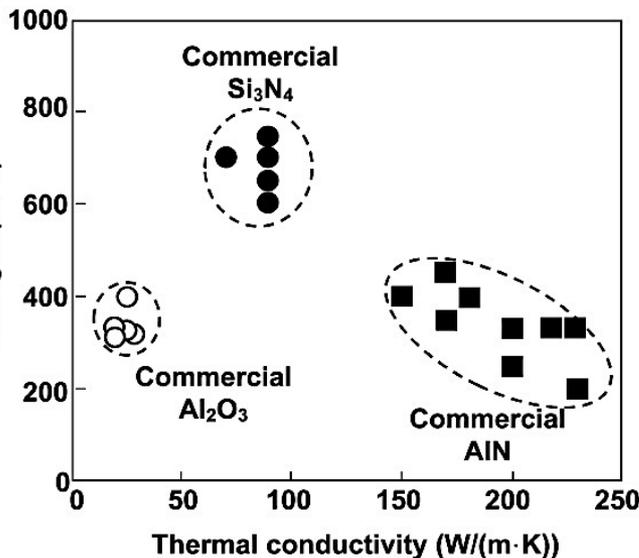
$\sigma = 400$   
MPa  
 $m = 13$   
 $K_{IC} = 3$   
 $\text{MPa}\cdot\text{m}^{0.5}$



$\sigma = 800$  MPa  
 $m = 18$   
 $K_{IC} = 6$   
 $\text{MPa}\cdot\text{m}^{0.5}$

FEA  
Wereszczak

Courtesy of  
Hirao Kiyoshi,  
AIST, Japan

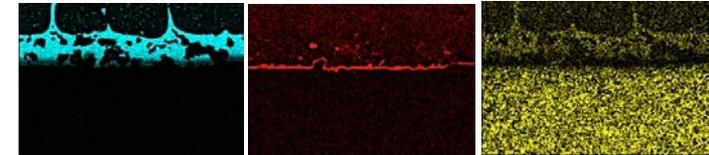
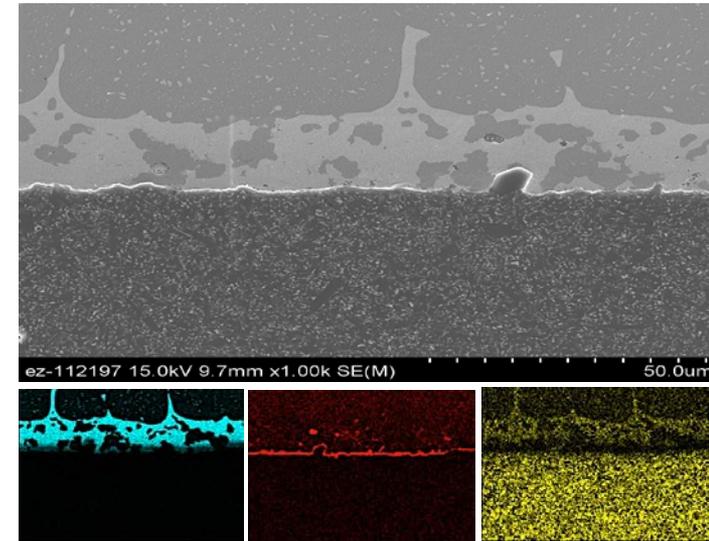
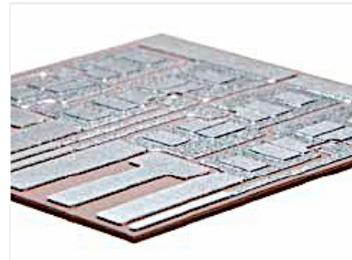
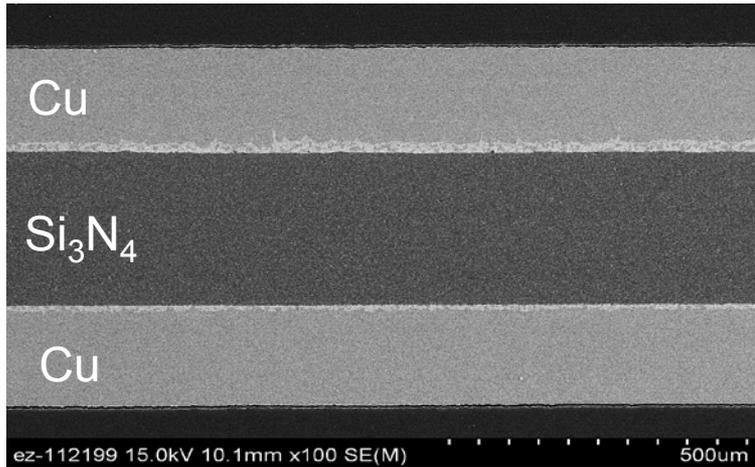


The use of  $\text{Si}_3\text{N}_4$  ceramic substrate (1/2 of AlN thickness) with excellent mechanical performance could minimize tensile stress and thus improve mechanical reliability

# Accomplishments (continued)

## Si<sub>3</sub>N<sub>4</sub> DBC Substrates Have Better Mechanical Reliability Than Traditional Substrates

### Kyocera AMT DBC



Ag

Ti

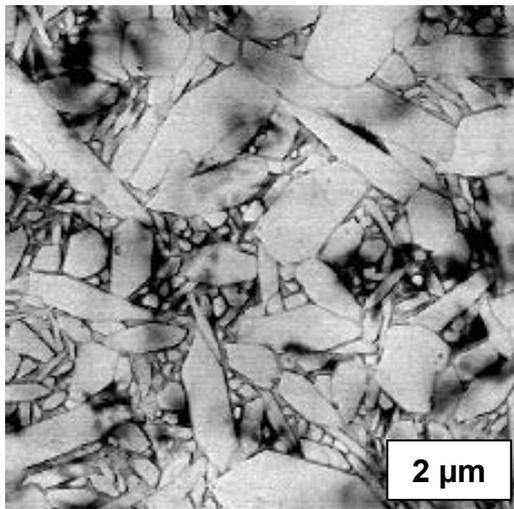
Mg

Supplier	Flexure Strength (MPa)	Fracture Toughness (MPa•√m)	Thermal Conductivity (W/m•k)
Commercial AlN	400	5	150 - 200
Kyocera SN460	850	5	60
Toshiba SN90	650	6.5	90
Curamic SN*	650	6.5 - 7	90

\*Curamic (Rogers Corp.) officially demonstrated new Si<sub>3</sub>N<sub>4</sub> DBC substrates at eCarTech, Munich, Oct 2012

# Accomplishments (continued)

## ORNL Si<sub>3</sub>N<sub>4</sub> Ceramics Exhibit Comparable or Superior Mechanical Properties to Commercial Ones



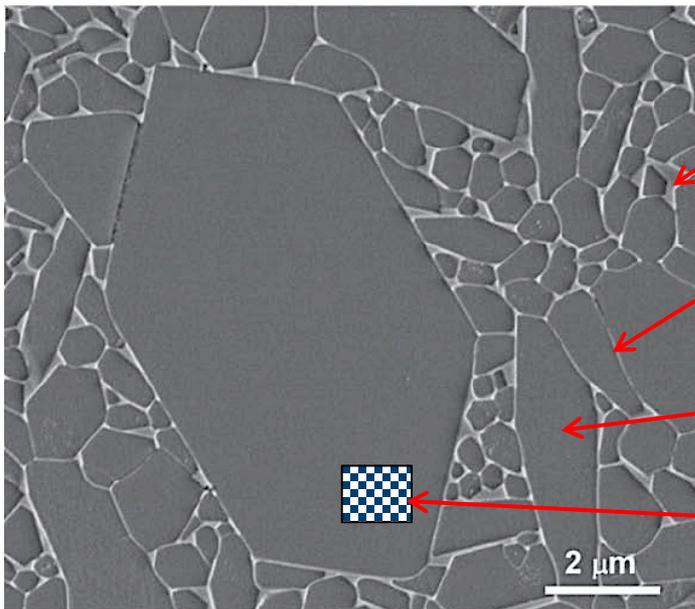
Composition	Flexure Strength MPa @ 22°C	Flexure Strength MPa @ 1200°C	Fracture Toughness MPa·√m
SN8La2Mg	1140	832	10-13
SN8Gd2Mg	1226	906	11
SN8Lu2Mg	1040	894	11-13
SN8La2Si	947	-	10
SN8Gd2Si	997	803	8
SN8Lu2Si	942	-	10
NT154	950	-	6
SN147	700-800	-	6
SN240	1000	-	10

*US patent: US 7,968,484 B2  
Becher and Lin*

- **SN** – developed by ORNL
- **NT154** – Saint-Gobain
- **SN147** – Ceradyne
- **SN240** - Kyocera

# Accomplishments (continued)

## Thermal Conductivity of $\text{Si}_3\text{N}_4$ Can be Tailored by Grain Boundary Microstructure and Chemistry

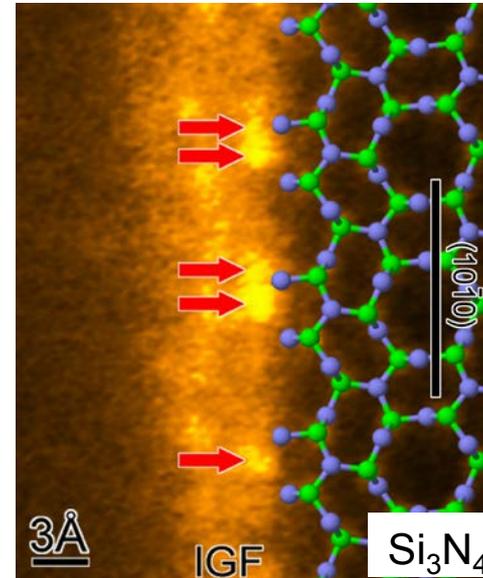


Secondary phase

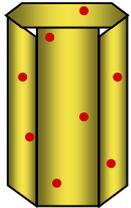
Grain boundary thin film (nm)

$\beta\text{-Si}_3\text{N}_4$  grain

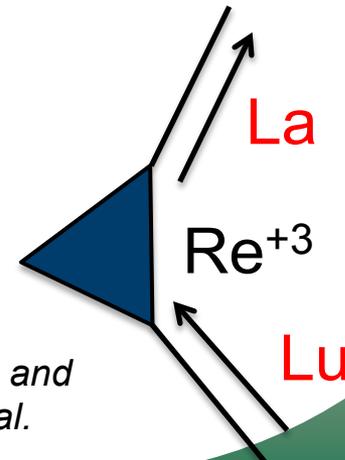
Lattice defects (lattice oxygen)



Lu



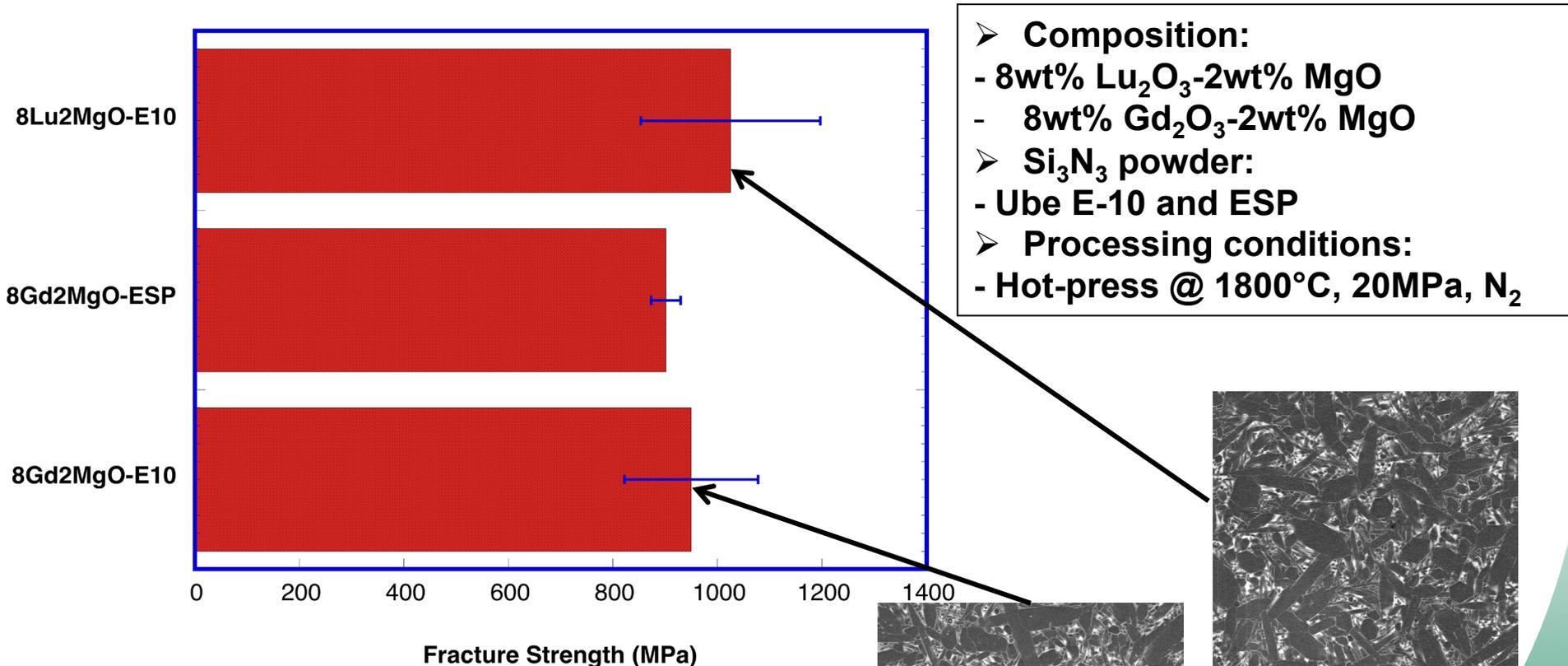
**2<sup>nd</sup> phases, GB film (low thermal property) and lattice oxygen (more phonon scattering) could lower the thermal conductivity of  $\text{Si}_3\text{N}_4$  ceramics**



by Shibata and Becher et al.

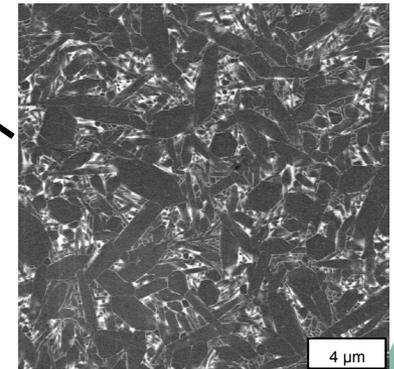
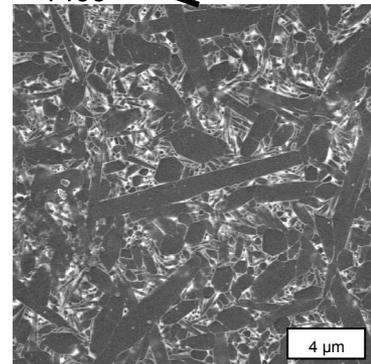
# Accomplishments (continued)

## Mechanical Strength of ORNL Si<sub>3</sub>N<sub>4</sub> Ceramics Confirmed



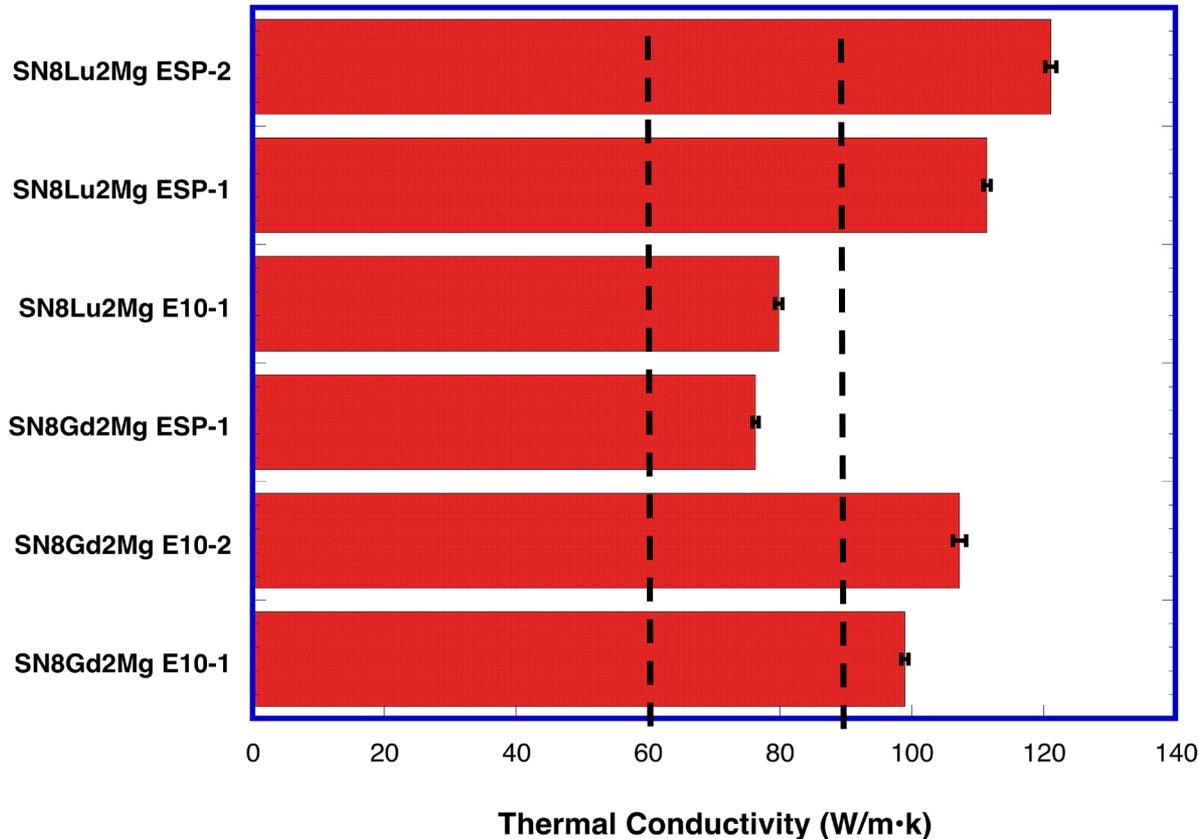
- **Composition:**
  - 8wt% Lu<sub>2</sub>O<sub>3</sub>-2wt% MgO
  - 8wt% Gd<sub>2</sub>O<sub>3</sub>-2wt% MgO
- **Si<sub>3</sub>N<sub>3</sub> powder:**
  - Ube E-10 and ESP
- **Processing conditions:**
  - Hot-press @ 1800°C, 20MPa, N<sub>2</sub>

**950-1100 MPa: flexure strength of ORNL specimens fabricated in 2010; JACS, 93 [2] 570-580 (2010)**



# Accomplishments (continued)

## ORNL $\text{Si}_3\text{N}_4$ Ceramics Exhibit Comparable or Superior Thermal Conductivity to Commercial $\text{Si}_3\text{N}_4$



- Kyocera SN460:  
60  $\text{W/m}\cdot\text{k}$

- Toshiba SN90:  
90  $\text{W/m}\cdot\text{k}$

- Curamic SN:  
90  $\text{W/m}\cdot\text{k}$

Manufacturers reported data

*Measured by laser flash method*

Thermal property could be further enhanced by engineering control of  $\text{Si}_3\text{N}_4$  grain size, oxygen content, and crystallinity of 2<sup>nd</sup> phase

# Collaborations

## ➤ Partners

- ✓ **Advanced Power Electronics and Electric Motors R&D team members at NTRC of ORNL.**
- ✓ **Electric and Electronic Tech Team provided constructive input.**
- ✓ **Marlow (established thermoelectric manufacturer) provided their DBA substrate for ORNL to assess and conduct bench mark test.**
- ✓ **Materion provided the Cu-clad Al ribbon with tailored thermal and electric property.**

## ➤ Technology transfer

- ✓ **Potential with Marlow, GM or Delphi on the development of high performance DBA/DBC substrates with  $\text{Si}_3\text{N}_4$  ceramic substrate.**
- ✓ **Development of high performance DBA substrate with  $\text{Si}_3\text{N}_4$  ceramic substrate would provide the high-power and high-temperature challenge for IGBT and MOSFET with SiC or GaN wide band gap material.**

# Future Work

- **Complete fabrication of tape-cast Al-Si thin film using atomization Al-Si powders for bonding Al-AlN (and Al<sub>2</sub>O<sub>3</sub>) substrates. (FY 13)**
- **Complete fabrication of tape-cast Si thin film using commercial Si powders for bonding Al-AlN (and Al<sub>2</sub>O<sub>3</sub>) substrates. (FY13)**
- **Complete optimization of Si<sub>3</sub>N<sub>4</sub> ceramic with both high mechanical and thermal properties for power electronic ceramic substrates. (FY14)**
- **Develop low-cost Si<sub>3</sub>N<sub>4</sub> ceramic using high purity Si powders via sinter-reaction bonded process. (FY14)**
- **Fabricate DBC (and DBA) substrates using reaction-bonded Si<sub>3</sub>N<sub>4</sub> ceramics via Ti-containing active brazing element, and tech transfer and commercialize the products. (FY15)**

# Summary

- **Relevance:** low cost and robust DBA substrates to improve reliability of power electronic device.
- **Approach:** develop low cost and reliable DBA substrates with AlN and Si<sub>3</sub>N<sub>4</sub> ceramic via brazing and/or metallurgical process.
- **Collaboration:** EETT, substrate manufacturers, and materials suppliers.
- **Technical Accomplishments:**
  - ✓ Results confirm compromise between low cost and reliability must be struck.
  - ✓ Processing and characterization of DBA substrates with Al-Si paste and Al-Si foil.
  - ✓ Characterizations of Al-Si and Si powders
  - ✓ Re-produce ORNL Si<sub>3</sub>N<sub>4</sub> ceramics with consistent excellent mechanical strength
  - ✓ Thermal property measurements of ORNL Si<sub>3</sub>N<sub>4</sub> ceramics
- **Future Works:**
  - ✓ Optimization of Si<sub>3</sub>N<sub>4</sub> ceramic with both high mechanical and thermal properties.
  - ✓ Development low-cost Si<sub>3</sub>N<sub>4</sub> ceramic using high purity Si powder
  - ✓ Fabrication of DBC (and DBA) substrates using reaction-bonded Si<sub>3</sub>N<sub>4</sub> ceramics and tech transfer and commercialize the products.